Amendments to the Claims

This listing of claims will replace all prior versions, and listings, of claims in the application:

Listing of Claims:

Claims 1 through 30 (Canceled).

Claims 31 through 43 (Canceled).

44. (Currently Amended) A process for removing a substance from at least a portion of the surface of a reaction chamber, the process comprising:

providing a reaction chamber wherein at least a portion of the surface is at least partially coated with the substance and wherein the substance has a dielectric constant of 4.1 or greater and is at least one member of the group consisting of a transition metal oxide, a transition metal silicate, a Group 13 metal oxide, a Group 13 metal silicate, a nitrogen containing Group 13 metal oxide, a nitrogen containing Group 13 metal silicate, a nitrogen containing transition metal oxide, a nitrogen containing transition metal silicate, or a laminate comprising at least one layer of the group consisting of a transition metal oxide, a transition metal oxide, a Group 13 metal oxide, a Group 13 metal oxide, a nitrogen containing Group 13 metal oxide, a nitrogen containing Group 13 metal oxide, a nitrogen containing transition metal silicate;

introducing a reactive agent into the reaction chamber wherein the reactive agent comprises at least one fluorine containing compound and at least one halogen-containing other compound selected from the group consisting of a chlorine-containing compound, a bromine-containing compound, or and an iodine-containing compound, wherein the amount of fluorine-containing compound is less than 50% by volume of an amount of the halogen-containing at least one other compound;

exposing the reactive agent to one or more energy sources sufficient to react the substance with the reactive agent and form a volatile product; and removing the volatile product from the reaction chamber.

- 45. (Previously Presented) The process of claim 44 wherein the reactive agent further comprises at least one member selected from the group consisting of a boron-containing compound, a carbon-containing compound, a hydrogen-containing compound, a chelating compound, a chlorosilane compound, a hydrochlorosilane compound, and an organochlorosilane compound.
- 46. (Previously Presented) The process of claim 44 wherein the reactive agent is exposed to one or more energy sources and the exposing step is conducted prior to the introducing step.
- 47. (Previously Presented) The process of claim 44 wherein the reactive agent is exposed to one or more energy sources and the exposing step is conducted during at least a portion of the introducing step.
- 48. (Previously Presented) The process of claim 44 wherein a temperature of the exposing step is at least 150 °C.
- 49. (Previously Presented) The process of claim 44 wherein a pressure of the exposing step is at least 10 mTorr.

Claims 50-51 (Canceled).

- 52. (New) The process of claim 44 wherein the reactor is an atomic layer deposition reactor.
- 53. (New) The process of claim 44 wherein the substance is at least one member selected from the group consisting of Al₂O₃, HfO₂, ZrO₂, HfSi_xO_y, ZrSi_xO_y, where x

is greater than 0 and y is 2x + 2, $Al_2Si_wO_z$, where w is greater than 0 and z is 2w + 3, or any of the aforementioned compounds containing nitrogen.

- 54. (New) The process of claim 44 wherein the substance is a laminate comprising layers of at least one material selected from the group consisting of a transition metal oxide, a transition metal silicate, a Group 13 metal oxide, a Group 13 metal silicate, a nitrogen containing transition metal oxide, a nitrogen containing transition metal oxide, or a nitrogen containing Group 13 metal silicate.
- 55. (New) The process of claim 44 wherein the at least one other compound is a chlorine-containing compound selected from the group consisting of BCl₃, COCl₂, HCl, CIF₃, NF_zCl_{3-z}, where z is an integer from 0 to 2, and mixtures thereof.
- 56. (New) The process of claim 55 wherein the chlorine-containing compound is BCl₃.
- 57. (New) The process of claim 44 wherein the at least one other compound is a chlorine-containing compound having the formula C_xH_yCl_z, wherein x is a number ranging from 1 to 6, y is a number ranging from 0 to 13, and z is a number ranging 1 from 14.
- 58. (New) The process of claim 44 wherein the reactive agent is conveyed to the substance from a gas cylinder, a safe delivery system, or a vacuum delivery system.
- 59. (New) The process of claim 44 wherein the reactive agent is formed in situ by a point-of-use generator.

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60. (New) The process of claim 44 wherein the substance is contacted with the reactive agent diluted with an inert gas diluent.